

HIGH RESISTIVITY TRANSITION EDGE SENSOR MODELLING AND EXPECTED PERFORMANCES

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- Multiplexing increasingly difficult with the number of pixel.

- the other as a sensor)
- thermometer is very small compared to the Joule power of the heating device.

Thermal model

Thermal model



> Five thermal baths:

- Cold bath (T0), bulk phonon bath (Tb), absorber (Ta), sensor and heating device electron bath (Ts, Th)
- Every bath is exchanging thermal power through thermal resistance and is characterised by its thermal capacity
- Phonons of the sensor and the heating device are well thermally coupled to the silicon bulk.

> Three power sources:

- The incident photon power on the absorber
- The Joule effect on the sensor caused by the bias
- The heating Joule controlled by the active electrothermal feedback

\succ Links to the electrical feedback/readout:

- The Ts bath is responsible for the signal and is directly connected to the amplifier input
- The output of the electronics is connected to the heating device which produces a large Joule effect responsible for the bulk temperature
- This model is translated into a fully electrical model with the electrical/thermal analogy

Numerical study of the model



• Numerical simulation to compare model and measurements in time domain

> Model versus measurements:

- Every parameter is expressed with literature definitions but controlled by the measurements. The model gives very similar data as actual TES measurements.
- Without feedback we observe the effect of the thermal capacities variations due to temperature. The same heat impulse gives longer signals as the temperature increase and therefore higher thermal capacities.
- With feedback we observe similar time behaviour for a 14.5 keV pulse, but this need to be perfected with less noisy measurements.
- A new campaign of measurements is planned with the great improvements in

Analytical study of the model

> Purpose:

- Have a better understanding of the frequency behaviour of the system and its noises
- Tool to enlighten parameters' influences over the spectral resolution

> Analytical model:

- The electrothermal model is expressed as a block diagram
- Each block represents either a thermal component (capacity or resistance), an electrical function of the model (Joule effects or amplifier transfer function) or the dR/dT parameter of the NbSi measured.
- Every function is linearised and then transformed into the Laplace domain
- The diagram can be simplified and gives the total transfer function that expresses the voltage output with the input photon power.
- Every noise source is identified and placed on the diagram. It can be simplified again with the noise as input.

> Noise:

- A total of 6 noises are identified: sensor and heating Johnson noises, amplifier, thermal noises from the pixel to cold bath link and from the absorber to the pixel link, and the electrons/phonons decoupling noise.
- We can derive the NEP from the transfer function of those noises by dividing them by the total input transfer function.

> Spectral resolution:

- The maximum performance that can be expected is directly derived from NEPs
- The model can then easily predict the best resolution for given parameters of our system.
- For the actual pixel, we can expect 14.4 eV of spectral resolution as it is unoptimised

Conclusion

Pixel optimisation

Noise spectrum computed with the analytical tool

> Optimisation:

- The model **computes noise spectrum** for input parameters that are tuneable in the development of the detector.
- Every modification of any parameter is **automatically taken into account** on every other related parameters.
- It renders optimisation much easier and is necessary as the feedback loop have some very unintuitive effects.

> Steps:

- Lowering the temperature isn't necessarily the best option. Heat capacities decrease but el/ph decoupling increases and becomes too problematic. An optimal temperature for the NbSi is found at 110 mK. It helps improving the spectral resolution to **11.6 eV**
- Size can be of **500 µm x 500 µm for a pixel**, lowering the resolution to **5.56 eV**
- The volume of the NbSi deposition is a factor in both capacity and decoupling. And optimal is found at 2 e-9 cm³. The NbSi used as an heating device can be replaced by a lighter material too so we can achieve 4.13 eV.
- The thermal link to the cold bath has to be lowered to a minimum before the signal becomes too slow. All steps completed, a 1.54 eV resolution can be expected

> Expected resolution:

- We have developed a complete and accurate model of our NbSi pixel which fits measurements.
- The model shows that we can achieve outstanding performances:

1,54 eV resolution for an average size pixel

- A new measurement campaign will soon start with great improvement in noise performances and with an iron source in order to compute a spectrum.
- Furthermore, preliminary simulation shows that such feedback can be integrated the temporal in multiplexing of 32 pixels.

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